

FORM PTO-1449 MODIFIED

**INFORMATION DISCLOSURE CITATION  
IN AN APPLICATION**

APPLICATION (new) Based on Intl. App  
PCT/IT2003/000363  
FILING DATE: (new)  
FIRST NAMED INVENTOR: .Speciale  
GROUP ART UNIT:  
ATTORNEY DOCKET NO.: 47966.12.1

**U.S. PATENT DOCUMENTS**

Examiner Initials	Cite No. <sup>1</sup>	Document No. Number-Kind Code <sup>2</sup>	Date MM-DD- YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
dy		2002/0090454A1	07/11/2002	Paisley et al.	
dy		2004/0020436A1	02/05/2004	Kaeppler et al.	(equiv to WO02/38838)
dy		4,667,076	05/19/1987	Amada	
dy		4,794,217	12/27/1988	Quan et al.	
dy		4,860,687	08/29/1989	Frijlink	
dy		5,221,356	06/22/1993	Hillier et al.	
dy		5,695,567	12/09/1997	Kordina et al.	
dy		5,788,777	08/04/1998	Burk, Jr.	
dy		5,792,257	08/11/1998	Kordina et al.	
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dy		5,155,062	10/13/1992	Coleman	
dy		4,593,168	06/03/1986	Amada	

**FOREIGN PATENT DOCUMENTS**

Examiner Initials	Cite No. <sup>1</sup>	Foreign Patent Document Country Code <sup>3</sup> -Number <sup>4</sup> -Kind Code <sup>5</sup> (if known)	Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>6</sup>
dy		WO02/38838	05/16/2002			<input type="checkbox"/>
dy		WO02/38839	05/16/2002			<input type="checkbox"/>
dy		GB 1 458 222	12/08/1976			<input type="checkbox"/>
dy		FR 2 650 841	02/15/1991		(Engl. abst. from corresp. WO91/02105)	<input type="checkbox"/>

**NON-PATENT LITERATURE DOCUMENTS**

Examiner Initials	Cite No. <sup>1</sup>		T <sup>2</sup>
dy		Zhang, J., et al., "Growth Characteristics of SiC in a Hot-Wall CVD Reactor with Rotation", Journal of Crystal Growth 241 (2002) pp. 431-438	<input type="checkbox"/>
			<input type="checkbox"/>
			<input type="checkbox"/>

DATE CONSIDERED

4/27/06

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